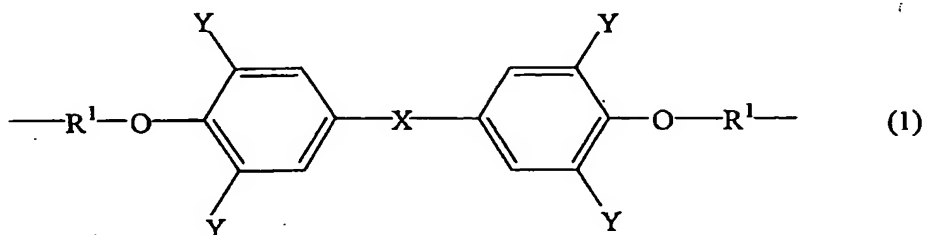


ABSTRACT

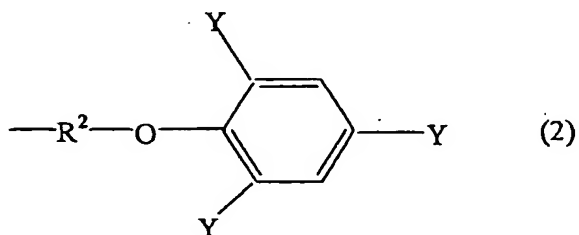
A photosensitive resin composition for optical waveguide formation, comprising:

- 5 (A) a di(meth)acrylate having the structure represented by the following general formula (1):



- (wherein R^1 is $\text{---(OCH}_2\text{CH}_2)_m\text{---}$, $\text{---(OCH(CH}_3\text{)CH}_2)_m\text{---}$, or $\text{---OCH}_2\text{CH(OH)CH}_2\text{---}$; X is $\text{---C(CH}_3\text{)}_2\text{---}$, $\text{---CH}_2\text{---}$, ---O--- , or $\text{---SO}_2\text{---}$; Y is a hydrogen atom or a halogen atom; m is an integer of 0 to 4);

- (B) a mono(meth)acrylate having the structure represented by the following general formula (2):



(wherein R^2 is $-(OCH_2CH_2)_p-$, $-(OCH(CH_3)CH_2)_p-$, or $-OCH_2CH(OH)CH_2-$; Y is a hydrogen atom, a halogen atom, $Ph-C(CH_3)_2-$, $Ph-$, or an alkyl group having 1 to 20 carbon atoms; p is an integer of 0 to 4; Ph is a phenyl group); and

- 5 (C) a photoradical polymerization initiator. The composition has excellent patterning ability, refractive index, heat resistance, and transmission characteristic.